



INFORMATION DISCLOSURE CITATION PTO-1449	Atty. Docket No. 032154	Serial No. 10/731,163
	Applicant(s): Mamoru NAKASUJI et al.	
	Filing Date: December 10, 2003	Group Art Unit: Unassigned

U.S. PATENT DOCUMENTS

Examiner Initial		Document No.	Name	Date	Class	Subclass	Filing Date (If appropriate)
KF	AA	3,777,211	Kuijpers	12/4/73	315	31 R	8/25/71
	AB	4,363,995	Takigawa et al.	12/14/82	313	346 R	9/23/80
	AC	4,743,766	Nakasuji et al.	5/10/88	250	492.2	7/17/87
	AD	5,854,490	Ooach et al.	12/29/98	250	492.23	7/16/96
	AE	6,087,667	Nakasuji et al.	7/11/00	250	492.2	9/30/97
KF	AF	6,107,636	Muraki	8/22/00	250	492.2	5/21/98

FOREIGN PATENT DOCUMENTS

		Document No.	Date	Country	Translation (Yes or No)
KF	AG	64-084629	3/29/89	Japan	Abstract
	AH	WO 01/09922 A1	2/8/01	WIPO	
	AI	WO 02/01596 A1	1/3/02	WIPO	Corresponds to U.S. Appln. No. 09/891,511
	AJ	WO 02/01597 A1	1/3/02	WIPO	Corresponds to U.S. Appln. No. 09/891,611
	AK	WO 02/37527	5/10/02	WIPO	Corresponds to U.S. Appln. No. 09/985,323
	AL	WO 02/13227	2/14/02	WIPO	Corresponds to U.S. Appln. No. 09/891,612
KF	AM	WO 02/40980	5/23/02	WIPO	Corresponds to U.S. Appln. No. 09/985,331

Examiner	KF	Date Considered	9-10-05
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Group Art Unit: Unassigned

OTHER DOCUMENTS		
KF	AN	"The Detection and Measurement of Infra-Red Radiation" Smith et al.; 1968
	AO	"Promising cathode materials for high brightness electron beams" J. Vac. Sci. Technol., B2(1), (1984), Shigeaki Zaima, et al.; pp73-79
	AP	"Reduction Mechanism for Spherical and Chromatic Aberration Coefficients of Magnetic Lens and Retarding Electric Fields" JPN. J. Appl. Phys. Vol. 32 (1993) M. Nakasuj, et al.; pp4819-4825
	AQ	"Advance deflection concept for large area, high resolution e-beam lithography" J. Vac. Sci. Technol., 19(4) (1981), H.C. Pfeiffer, et al.; pp1058-10-63
KF	AR	Electronic Beam Testing Handbook Vol. 7 pp64-65, 3.3.A Shot Noise (with a partial English translation within brackets)
Examiner <u>KF</u> Date Considered <u>9-10-05</u>		